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## AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings of claims in the application:

## **LISTING OF CLAIMS**

- 1. (Previously Presented) X-radiation imagery device comprising at least one detection matrix made of a semiconducting material comprising pixels to convert incident X-photons into electric charges and an electric charges reading panel comprising several electronic devices, each electronic device being integrated by pixel, characterized in that each detecting matrix includes a detection layer made of a continuous layer of semiconducting material deposited in vapour phase on the electric charges reading panel.
- 2. (Currently Amended) Process for making an X-radiation imagery device comprising at least one detecting matrix made of a semiconducting material comprising pixels pixels, to convert incident X-photons into electric charges, and an electric charges reading panel based on silicon comprising several electronic devices, each electronic device being integrated by pixel, characterized in that each detecting matrix is obtained by vapour phase deposition of a semiconductor on the electric charges reading panel, each detecting matrix including a detection layer made of a continuous layer of semiconducting material.

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3. (Previously Presented) Process according to claim 2, in which the evaporation properties of this semiconductor are such that the deposition can be done at a temperature lower than a temperature that damages the electronic devices.

- 4. (Original) Process according to claim 2, in which the semiconducting material used to make the matrix of detection pixels is CdTe, HgI<sub>2</sub> or PbI<sub>2</sub>.
- 5. (Previously Presented) Process according to claim 2, in which electronic devices made using a process technology having a feature device size of 1.25 μm are used.
- 6. (Previously Presented) Process according to claim 2, in which electronic devices made using a process technology having a feature device size of 0.1 μm are used.
- 7. (Previously Presented) X-radiation imagery device according to claim 1, further characterized in that the detection layer is deposited directly on the electronic devices of the electric charges reading panel in each pixel.
- 8. (Previously Presented) X-radiation imagery device according to claim 1, further characterized in that the semiconducting material of the detection layer is crystalline silicon.